

Lawrence Berkeley National Laboratory

Recent Work

Title

LARGE AREA NON-CRYSTALLINE SEMICONDUCTOR DETECTORS

Permalink

<https://escholarship.org/uc/item/2f69n4wp>

Author

Perez-Mendez, V.

Publication Date

1983-03-01

22



Lawrence Berkeley Laboratory

UNIVERSITY OF CALIFORNIA

RECEIVED

LAWRENCE BERKELEY LABORATORY

Physics, Computer Science & Mathematics Division

MAY 17 1983

LIBRARY AND DOCUMENTS SECTION

Presented at the American Physical Society
Division of Particles and Fields Workshop
on Hadron Collider Detectors, Lawrence Berkeley
Laboratory, University of California, Berkeley, CA,
February 28-March 4, 1983

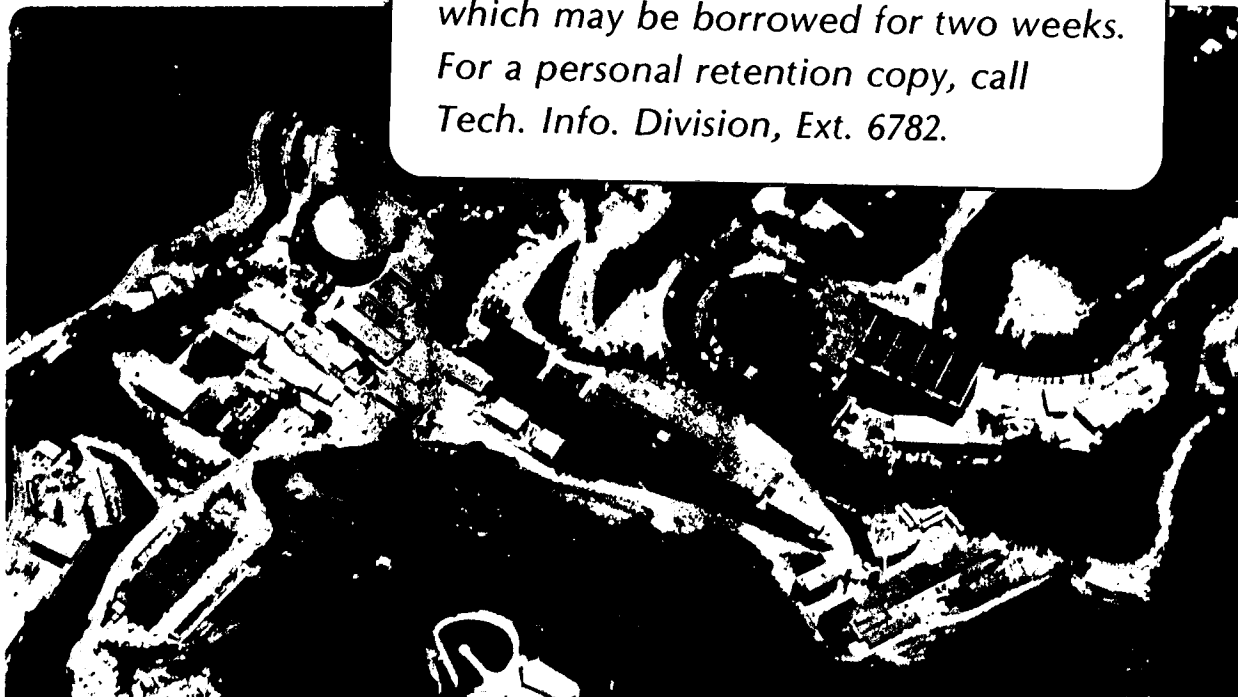
LARGE AREA NON-CRYSTALLINE
SEMICONDUCTOR DETECTORS

V. Perez-Mendez, T. Mulera, S.N. Kaplan, and
P. Wiedenbeck

March 1983

TWO-WEEK LOAN COPY

*This is a Library Circulating Copy
which may be borrowed for two weeks.
For a personal retention copy, call
Tech. Info. Division, Ext. 6782.*



LBL-15866
22

DISCLAIMER

This document was prepared as an account of work sponsored by the United States Government. While this document is believed to contain correct information, neither the United States Government nor any agency thereof, nor the Regents of the University of California, nor any of their employees, makes any warranty, express or implied, or assumes any legal responsibility for the accuracy, completeness, or usefulness of any information, apparatus, product, or process disclosed, or represents that its use would not infringe privately owned rights. Reference herein to any specific commercial product, process, or service by its trade name, trademark, manufacturer, or otherwise, does not necessarily constitute or imply its endorsement, recommendation, or favoring by the United States Government or any agency thereof, or the Regents of the University of California. The views and opinions of authors expressed herein do not necessarily state or reflect those of the United States Government or any agency thereof or the Regents of the University of California.

Large Area Non-Crystalline Semiconductor Detectors

V. Perez-Mendez, T. Mulera, S.N.Kaplan, P. Wiedenbeck
Lawrence Berkeley Laboratory, University of
California, Berkeley, CA 94720

Summary

The properties of various non-crystalline semiconductors are considered for use as position sensitive detectors. Amorphous silicon and conducting plastic can be doped to form NP depletion regions similar to those in single crystal silicon, but without the limitation of single crystal size. Chalcogenide glassy materials such as Te-Se-Ge compounds as well as some metallic oxides such as the Vanadium oxides have switching and memory properties. They could serve as x,y location identifying devices when triggered by amplified pulses from a parallel plate or multistep gas filled detector stage in order to resolve the multitrack ambiguity for x,y readout schemes.

I. Introduction

Single crystal semiconductor detectors have been widely used in Nuclear Physics research as energy measuring devices. For γ spectrometry in the few KeV to MeV energy range, back biased NP junction Germanium single crystals of ultra-pure germanium have given the highest energy resolution of any device. Position sensitive detection of charged particles has been done with back biased NP junctions in silicon crystals with a plated metallic grid to give the position information. In high energy physics these devices have come into use as vertex detectors in colliding beam accelerators, with spatial resolutions in the few tens of microns range.

All of these applications of silicon and germanium semiconductor detectors are limited to small area usage by the fact that they are slabs of single crystal material. Larger area devices could be made by use of a mosaic of crystals at a high cost and with a great deal of electronic complexity. Furthermore, if the events which traverse the crystal have a high multiplicity, the usual multi-track ambiguity from crossed grid detectors is still present.

We propose to develop the properties of three classes of non crystalline semiconductors for uses as radiation detectors, which would not be subject to the above mentioned limitations. These are (a) Amorphous silicon; (b) semiconducting plastics and (c) chalcogenide - Metallic oxide compounds.

Both amorphous silicon and semiconducting plastics - primarily polyacetylene - can be doped by suitable materials to form N or P type layers and thus create a depletion region by back biasing in the usual manner. Since both of these materials are non-crystalline, the limitations as to size do not apply; however, the difficulty with the multi-track ambiguity still remains.

Amorphous silicon can be deposited in large areas by various processes such as the decomposition of Silane- S_2H_4 ¹. Doping with trivalent and pentavalent impurities can be done by vacuum deposition, or by sputtering techniques. The mobility of the electrons and holes in this material is appreciably slower than in the

single crystal silicon,² and thus there may be serious limitations to the resolving time of such layers if they are more than a few microns thick. Multiple layers can presumably be made in order to have a sufficient stopping power for detection of minimum ionizing particles. Amorphous silicon, being non-crystalline is less susceptible to radiation damage than its crystalline counterpart.

The development of conducting plastics has occurred primarily during the last few years. Among the various types³ the most promising at this point is Polyacetylene which can be made by vacuum techniques⁴ in layers up to a few m.m. thick. Doping with trivalent and pentavalent impurities for PN junctions formation can be done by electrolytic methods⁵ or by deposition from the gaseous phase.⁶ One present difficulty with the conducting Polyacetylene is that it is unstable in the presence of oxygen; this difficulty can, however, be readily resolved by encapsulation with thin mylar sheets.

A third approach to large area solid state detectors is to use the switching properties of some chalcogenide (Se-Te-Ge-Si) and metallic oxide compounds. These materials switch from a high resistance state to a low resistance state; some under the action of an electric⁷ field and some at a critical temperature⁸. The Vanadium Oxides V_2O_3 and VO_2 for example switch at temperatures of 140°K and 68°C respectively. Some of the Se-Te-Ge-Si chalcogenides have been used as electronic latches in prototype computer memory arrays⁹. These devices can be made in large areas by vacuum deposition, sputtering and similar techniques. The temperature switching components are slower than the electronic switching compounds (10-100 μ sec compared to 1-20 nsec).

The switching compounds have the following useful features

- (a) They are readily made and there is some commercial background on their use
- (b) They are more radiation resistant than the semiconducting plastics
- (c) The switching properties and their memory can be used to resolve the multi track ambiguity when x,y crossed grid arrays are used.

Figure 1 shows the voltage current relation for typical electronically switched chalcogenides. Since traversal of a semiconducting layer by a charged particle will not produce a net potential difference across the layer, these materials could be used in conjunction with a gas filled chamber and serve as a memory at each node of an orthogonal grid of wires or plated strips similar to a glow chamber memory device¹⁰.

Figure 2 shows the configuration of an argon or neon filled chamber (with a suitable quenching gas), either working as a parallel plate chamber or in a multistep chamber configuration. The pulse of electrons (10^7 to 10^8 electrons) can be drifted onto a plated layer of chalcogenide material, causing switching at locations where charged particles traversed the chamber. A readout scheme in which the n^2 locations are sampled is shown in Fig. 3. Each x line is pulsed sequentially to switch off any conducting elements on that line. The corresponding y locations are read out in synchronism. The speed of such a readout can be as short as 10-20 n/sec per x wire, which is appreciably faster than the corresponding glow memory device.

References

1. W.E. Spear, *Adv. Physics* **26** (1977) 811.
2. R.S. Grandall, *J. App. Physics* **52** (1981) 1387.
3. A.G. MacDiarmid and A. J. Heeger, *Synthetic Metals I* (1979/80) 101.
4. C.K. Chiang et al., *App. Phys. Letters* **33** (1978) 18.
5. Y.W. Park et al., *Solid State Communications* **19** (1979) 747.
6. J.F. Kwak et al., *Synthetic Metals I* (1979/80) 213.
T. Tani et al., *Solid State Communications* **33** (1980) 499.
7. N.F. Mott and E.A. Davis, *Electronic Processes in Non-crystalline Materials*, Clarendon Press, Oxford (1979).
8. J.K. Higgins et al., *J. Non-Crys. Solids* **18** (1975) 77.
9. S.R. Ovshinsky, *Phys. Rev. Lett.* **20** (1968) 1450.
10. T. Mulera, M. Elola, V. Perez-Mendez, and P. Wiedenbeck, *IEEE Trans. Nuc.Sci.* **NS-24** (1982) 425.

This work was supported by the Director, Office of Energy Research, Office of High Energy and Nuclear Physics, Division of High Energy Physics of the U.S. Department of Energy under Contract No. DE-AC03-76SF00093.

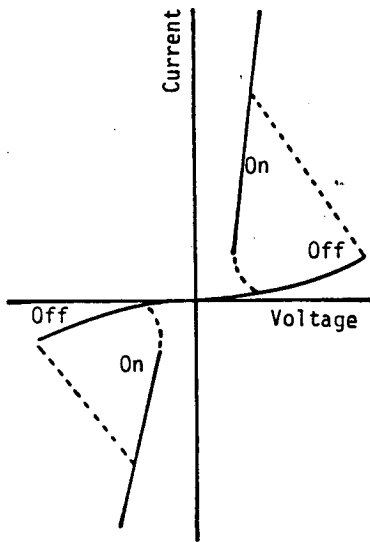


Fig. 1. Current voltage characteristic of a chalcogenide glass switch.

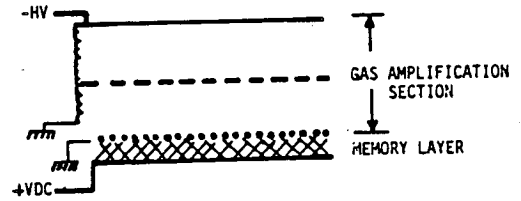


Fig. 2. Schematic of proposed detector. The gas amplification scheme shown here is a multi-step avalanche chamber.

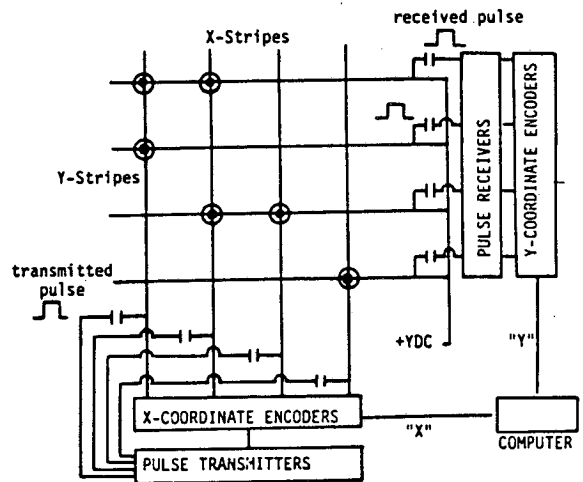


Fig. 3. The correlated x-y readout scheme. The circles represent memory elements which have been switched on by the passage of a charged particle at that location.

This report was done with support from the Department of Energy. Any conclusions or opinions expressed in this report represent solely those of the author(s) and not necessarily those of The Regents of the University of California, the Lawrence Berkeley Laboratory or the Department of Energy.

Reference to a company or product name does not imply approval or recommendation of the product by the University of California or the U.S. Department of Energy to the exclusion of others that may be suitable.

TECHNICAL INFORMATION DEPARTMENT
LAWRENCE BERKELEY LABORATORY
UNIVERSITY OF CALIFORNIA
BERKELEY, CALIFORNIA 94720